

## Patent Abstracts of Japan

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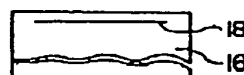
APPLICATION NUMBER : 09145855

APPLICANT : TOKYO ELECTRON LTD;

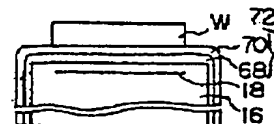
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INT.CL. : H01L 21/285 C23C 16/44

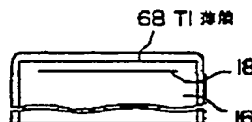
TITLE : FILM DEPOSITION METHOD AND FILM DEPOSITION DEVICE



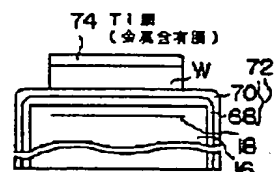
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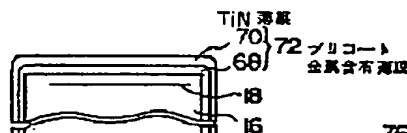
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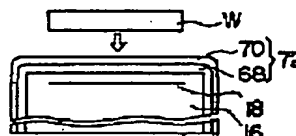
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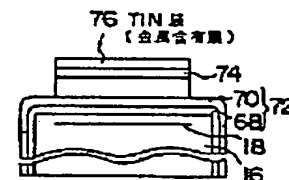
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(G)

ABSTRACT : PROBLEM TO BE SOLVED: To provide a film deposition method without heavy metallic contamination, even while using a metallic mounting base.

SOLUTION: In this film deposition method for forming a metal containing film to a processed body W mounted on a metallic mounting base 16 inside a processing container 4, a pre-coating metal containing a thin film 72 containing the same metal as a metal-containing film 74 is formed on the surface of the mounting base 16. Thereafter, the metal-containing film 74 is formed on the surface of the processed body W in the state of mounting the processed body W on the mounting base 16. Thus, by the pre-coating metal containing thin film, the metallic atoms of the mounting base 16 are suppressed from going outside so as to prevent from becoming the cause of the heavy metal contamination.

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